(FILE 'HOME' ENTERED AT 01:48:41 ON 19 JUN 2006)

FILE 'STNGUIDE' ENTERED AT 01:48:44 ON 19 JUN 2006

FILE 'HCAPLUS, INSPEC, JAPIO, USPATFULL, USPAT2' ENTERED AT 01:49:12 ON 19 JUN 2006

116168 S (LASER(8A) IRRADIAT?)

3019 S (CONTROL? OR ALTER? OR VARY? OR MANIPULAT?) (8A) (BEAM# (6A) SPEE

31222 S (PHASE) (10A) (FLUCTUAT? OR ENERG? (6A) FLUCTUAT?)

384576 S (LASER(W)BEAM#)

=> s 11 and 12 and 13 and 13

5 L1 AND L2 AND L3 AND L3

 \Rightarrow s 11 and 12 and 13

L1

L2

L3

L4

AΒ

ΤI

5 L1 AND L2 AND L3

=> d 16 1-5 abs,bib

ANSWER 1 OF 5 USPATFULL on STN L6

It is an object to provide a laser apparatus, a laser

irradiating method and a manufacturing method of a semiconductor device that can perform uniform a process with a laser beam to an object uniformly. The present invention provides a laser apparatus comprising an optical system for sampling a part of a laser beam emitted from an oscillator, a sensor for generating an electric signal including fluctuation in energy of the laser beam as a data from the part of the laser beam, a means for performing signal processing to the electrical signal to grasp a state of the fluctuation in energy of the

laser beam, and controlling a relative

speed of an beam spot of the laser

beam to an object in order to change in phase with the

fluctuation in energy of the laser beam.

2004:260750 USPATFULL ΑN

Laser apparatus laser irradiation nethod, and manufacturing method of semiconductor device Miyairi, Hidekazu, Tochigi, JAPAN Shimomura, Akihisa, Kanagawa, JAPAN Takano Taman Kanagawa, JAPAN

ΙN

Takano, Tamae, Kanagawa, JAPAN

Koyama, Masaki, Kanagawa, JAPAN C

PΑ Semiconductor Energy Laboratory Co., Ltd, Atsugi-shi, JAPAN (non-U.S.

corporation)

US 2004203248 20041014 US 2003-663671 20030917 (10) Α1

PRAI JP 2002-269655 20020917

DT Utility

FS APPLICATION

LREP NIXON PEABODY, LLP, 401 9TH STREET, NW, SUITE 900, WASHINGTON, DC,

20004-2128

CLMN Number of Claims: 10 ECL Exemplary Claim: 1

13 Drawing Page(s) DRWN

LN.CNT 665

L6 ANSWER 2 OF 5 USPATFULL on STN

AΒ It is an object to provide a laser apparatus, a laser

> irradiating method and a manufacturing method of a semiconductor device that make laser energy more stable. To attain the object, a part of laser beam emitted from an oscillator is sampled to generate an electric signal that contains as data energy fluctuation of a laser beam. The electric signal is subjected to signal processing to calculate the frequency, amplitude, and phase of the energy

fluctuation of the laser beam. The transmittance of a light amount adjusting means is controlled in order that the transmittance changes in antiphase to the phase of the energy

fluctuation of the laser beam and with an amplitude capable of

reducing the amplitude of laser beam emitted from the oscillator, the control being made based on the phase difference between the phase of a signal that is in synchronization with oscillation of laser beam emitted from the oscillator and the phase calculated, on the energy ratio of the sampled laser beam to laser beam emitted from the oscillator, and on the frequency and amplitude calculated. In the light amount adjusting means, energy of the laser beam oscillated from the oscillator energy is adjusted.

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2004:69054 USPATFULL
ΑN
ТT
       Laser apparatus, laser irradiation method,
       and manufacturing method of semiconductor device
       Miyairi, Hidekazu, Tochigi, JAPAN
ΙN
       Shimomura, Akihisa, Atsugi, JAPAN
       Takano, Tamae, Atsugi, JAPAN
       Koyama, Masaki, Atsugi, JAPAN
       Tanaka, Koichiro, Atsugi, JAPAN
PΑ
       Semiconductor Energy Laboratory Co., Ltd., Kanagawa-ken, JAPAN (non-U.S.
       corporation)
                               20040318
PΤ
       US 2004052279
                          Α1
                                20030910 (10)
AΤ
       US 2003-658472
                          Α1
PRAT
       JP 2002-268222
                           20020913
       JP 2002-274220
                           20020920
DТ
       Utility
FS
       APPLICATION
LREP
       NIXON PEABODY, LLP, 401 9TH STREET, NW, SUITE 900, WASINGTON, DC,
       20004-2128
CLMN
       Number of Claims: 16
ECT.
       Exemplary Claim: 1
DRWN
       14 Drawing Page(s)
LN.CNT 977
L6
     ANSWER 3 OF 5 USPATFULL on STN
AΒ
       A method of manufacturing a grating in an optical waveguide that
       includes a core and a cladding covering the core. The method includes
       the steps of providing the optical waveguide and scanning a laser beam
       along an optical axis of the optical waveguide to form modulation of
       refractive index of radiation in the core. The core is made of a
       material having the refractive index that is changeable by irradiation
       of radiation. In addition, on the step of scanning, in the core, the
       irradiation range of the laser beam is controlled and
       the laser beam is scanned a plurality of times. Therefore, predetermined
       distribution of irradiation amount is obtained in a direction of the
       optical axis of the grating.
       2002:156477 USPATFULL
AN
TI
       Method of manufacturing grating
ΙN
       Matsumoto, Sadayuki, Tokyo, JAPAN
       Ohira, Takuya, Tokyo, JAPAN
       Takabayashi, Masakazu, Tokyo, JAPAN
       Yoshiara, Kiichi, Tokyo, JAPAN
       Matsuno, Shigeru, Tokyo, JAPAN
       Takeya, Hajime, Tokyo, JAPAN
       Hoshizaki, Junichiro, Tokyo, JAPAN
PΙ
       US 2002081068
                          A1
                               20020627
       US 6690860
                          В2
                               20040210
AΙ
       US 2001-891319
                          Α1
                               20010627 (9)
PRAT
       JP 2000-394579
                           20001226
DT
       Utility
FS
       APPLICATION
LREP
       LEYDIG VOIT & MAYER, LTD, 700 THIRTEENTH ST. NW, SUITE 300, WASHINGTON,
       DC, 20005-3960
CLMN
       Number of Claims: 13
ECL
       Exemplary Claim: 1
DRWN
       14 Drawing Page(s)
LN.CNT 1550
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A method for measuring the speed of movement during beam track movement

L6

AΒ

ANSWER 4 OF 5 USPATFULL on STN

in an optical memory apparatus which moves a beam spot on a rotating optical recording medium, a beam spot is received from the optical recording medium and it is detected when the beam spot crosses a track. The number of the detected track crossings of the beam spot during a predetermined time are detected, and the interval of the detected track crossings is measured. The remainder time from the time when a track crossing is detected to the end of the predetermined time is counted, and the amount of movement of the beam spot in the predetermined time from the number of tracks counted, the time of the track crossing interval detected, and the remainder time detected, is measured.

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ΑN
       93:57558 USPATFULL
ΤI
       Method and apparatus for measuring speed of movement during beam track
       movement in optical memory apparatus
ΙN
       Yanagi, Shigenori, Kawasaki, Japan
PΑ
       Fujitsu Limited, Kawasaki, Japan (non-U.S. corporation)
PΤ
       US 5228019
                               19930713
       US 1990-506908
AΙ
                               1990041( (7)
PRAI
       JP 1989-90024
                           19890410
DТ
       Utility
FS
       Granted
EXNAM Primary Examiner: Psitos, Aristotelis; Assistant Examiner: Hindi, Nabil
LREP
       Staas & Halsey
CLMN
       Number of Claims: 8
ECL
       Exemplary Claim: 1
DRWN
       11 Drawing Figure(s); 8 Drawing Page(s)
LN.CNT 794
L6
     ANSWER 5 OF 5 USPAT2 on STN
AΒ
       A method of manufacturing a gratting in an optical waveguide that
       includes a core and a cladding covering the core. The method includes
       scanning a laser beam along an oatical axis of the optical waveguide to
       modulate the refractive index of the core. The core is made of a
      material having a refractive indek that is changeable upon irradiation
      by radiation. In addition, in scanning the core, the irradiation
       range of the laser beam is controlled and the core is scanned
       several times. Therefore, a predetermined distribution of irradiation is
       obtained in a direction of the optical axis of the grating.
       2002:156477 USPAT2
ΑN
TI
      Method of manufacturing grating
IN
      Matsumoto, Sadayuki, Tokyo, JAPAN
      Ohira, Takuya, Tokyo, JAPAN
      Takabayashi, Masakazu, Tokyo, JAPAN
      Yoshiara, Kiichi, Tokyo, JAPAN
      Matsuno, Shigeru, Tokyo, JAPAN
      Takeya, Hajime, Tokyo, JAPAN
      Hoshizaki, Junichiro, Tokyo, JAPAN
PΑ
      Mitsubishi Denki Kabushiki Kaisha, Tokyo, JAPAN (non-U.S. corporation)
PΙ
      US 6690860
                          B2
                               20040210
ΑI
      US 2001-891319
                               20010627 (9)
PRAI
      JP 2000-394579
                           20001226
DT
      Utility
FS
      GRANTED
EXNAM
      Primary Examiner: Ullah, Akm Enayet; Assistant Examiner: Stahl, Mike
      Leydig, Voit & Mayer, Ltd.
LREP
CLMN
      Number of Claims: 15
ECL
       Exemplary Claim: 1
DRWN
       25 Drawing Figure(s); 14 Drawing Page(s)
LN.CNT 1555
=>
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